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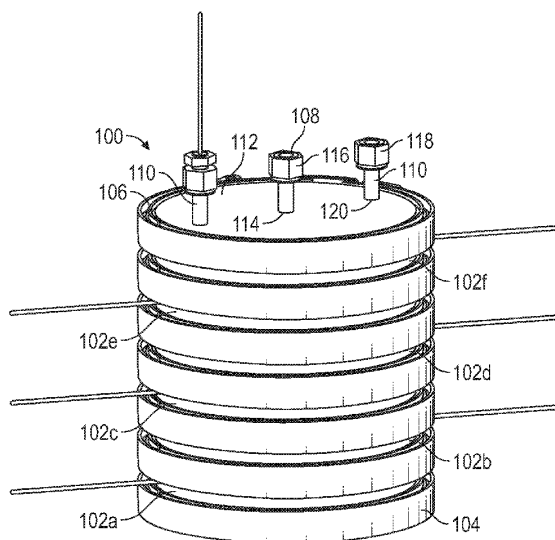


FIG. 1

(57) Abstract: A gas source includes a single tray or a plurality of trays including a top cover and a bottom cover, each tray including a source receiving portion and an outer circumferential wall having an outer wall surface, the outer circumferential wall including at least one projecting flange thereon, each projecting flange having an outer circumferential flange surface and a second surface extending from the circumferential flange surface in the direction of the outer wall surface, and a clamp, actuatable between a circumferentially expanded condition and a circumferentially reduced condition, wherein, in the circumferentially reduced position, contact the second surface of the first tray and the second surface of the second tray.

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